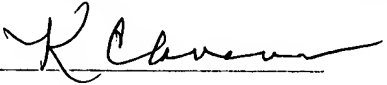


CERTIFICATE OF EXPRESS MAIL	
NUMBER	<u>EV 425193065 US</u>
DATE OF DEPOSIT	<u>3-26-24</u>
I hereby certify that this paper or fee is being deposited with the United States Postal Service "EXPRESS MAIL POST OFFICE TO ADDRESSEE" service under 37 C.F.R. 1.10 on the date indicated above and is addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria VA, 22313-1450.	
	
Signature	

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	§	Group Art Unit: unk
James Burdorf & Christophe Pierrat	§	
Assignee: Micron Technology, Inc.	§	Examiner: unk
Serial No.: unk	§	Examiner phone: unk
Filed: herewith	§	Atty. Dkt. No.: 102-0090US-C
For: <b>PROCESS FOR DETECTING DEFECTS</b>	§	
<b>IN PHOTOMASKS</b>	§	

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria VA, 22313-1450.

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56, it is respectfully requested that this Information Disclosure Statement (IDS) be entered and the documents listed on attached Form PTO-1449 be considered by the Examiner and made of record. Copies of the listed documents are attached.

In accordance with 37 C.F.R §§ 1.97(g),(h), this IDS is not to be construed as a representation that a search has been made, and is not to be construed to be an admission that the

information cited is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56(b), or that such information constitutes prior art.

This IDS is being filed prior to the receipt of a first Official Action reflecting an examination on the merits, and hence is believed to be timely filed in accordance with 37 C.F.R. § 1.97(b). No fees are believed to be due in connection with the filing of this IDS. However, the Commissioner is authorized to deduct any necessary fees from Deposit Account No. 501922, referencing matter no. 102-0090US-C.

Applicant respectfully requests that the listed documents be considered and made of record in the present case, and that the Examiner initial the appropriate spaces on the Form 1449 to evidence the same

Respectfully submitted,



Terril G. Lewis, Reg. No. 46,065

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Fax: 832 446-2424

3-26-2004

Form PTO-1449 (modified)	Atty. Docket No. 102-0090US-C	Serial No. unk
List of Patents and Publications for Applicant's  INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)	Inventor/Applicant: Christophe Pierrat et al./ Micron Technology, Inc.	
	Title: <b>PROCESS FOR DETECTING DEFECTS IN PHOTOMASKS</b>	
	Filing Date: herewith	Group:

### U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
	A1	4,633,504	12-30-86	Mark J. Wihl			6-28-84
	A2	4,926,489	5-15-90	Danielson, et al.			10-05-87
	A3	5,563,702	10-08-96	Emery, et al.			7-13-94
	A4	5,795,688	8-18-98	Burdorf, et al.			8-14-96
	A5	6,064,484	5-16-00	Kobayashi, et al.			3-11-97
	A6	4,527,070	7-02-85	Matsui, et al.			8-20-82
	A7	5,850,467	12-15-98	Matsui, et al.			11-15-94
	A8	5,029,222	7-02-91	Yamada, et al.			8-30-88
	A9	4,809,341	2-28-89	Matsui, et al.			7-13-87
	A10	5,307,421	4-26-94	Darboux, et al.			10-14-92
	A11	5,804,340	9-08-98	Garza, et al.			12-23-96
	A12	5,481,624	1-02-96	Kazuya Kamon			4-13-93
	A13	5,475,766	12-12-95	Tsuchiya, et al.			9-04-92
	A14	5,379,348	1-03-95	Watanabe, et al.			3-31-93
	A15	5,048,093	9-10-91	Kimura, et al.			4-11-90
	A16	5,306,585	4-26-94	Yoshihiko Okamoto			4-23-93
	A17	4,644,172	2-17-87	Sandland, et al.			2-22-84
	A18	5,129,009	7-07-92	Christopher J. Lebeau			6-04-90
	A19	4,893,346	1-09-90	Robert Bishop			9-02-87
	A20	5,707,765	1-13-98	Chen			5-28-96
	A21	5,725,974	3-10-98	Kawahira			6-28-96
	A22	5,441,834	8-15-95	Takekuma			9-10-92

**EXAMINER:**

**DATE CONSIDERED:**

EXAMINER: INITIAL IF REFERENCE CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.

Form PTO-1449 (modified)	Atty. Docket No. 102-0090US-C	Serial No. unk	2
List of Patents and Publications for Applicant's  INFORMATION DISCLOSURE STATEMENT  (Use several sheets if necessary)	Inventor/Applicant: Christophe Pierrat et al./ Micron Technology, Inc.		
	Title: <b>PROCESS FOR DETECTING DEFECTS IN PHOTOMASKS</b>		
	Filing Date: herewith	Group:	

### U.S. Patent Documents

Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.
	A23	5,125,040	6-23-92	Matsui			9-24-90
	A24	5,862,058	1-19-99	Samuels et al.			5-16-96
	A25	5,849,440	12-15-98	Lucas et al.			1-29-97

### Foreign Patent Documents

Exam. Init.	Ref. Des.	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes/No
	B1	0485274A2	5-13-92	Europe			Yes
	B2	138639	Apr. 1995	Europe			Yes

### Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation
	C1	S. Takeuchi, et al., "Advanced 5x reticle inspection technologies for ULSI devices," Integrated Circuit Metrology, Inspection, and Process Control IV, Vol. 1261, 1990, pp. 195-205.
	C2	Splat v5.0 Users' Guide (U. California Berkeley) (Jan. 19, 1995).
	C3	S. Wolf et al., "Silicon Processing," Vol. 1, Lattice Press, pg. 483-485.

**EXAMINER:**

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